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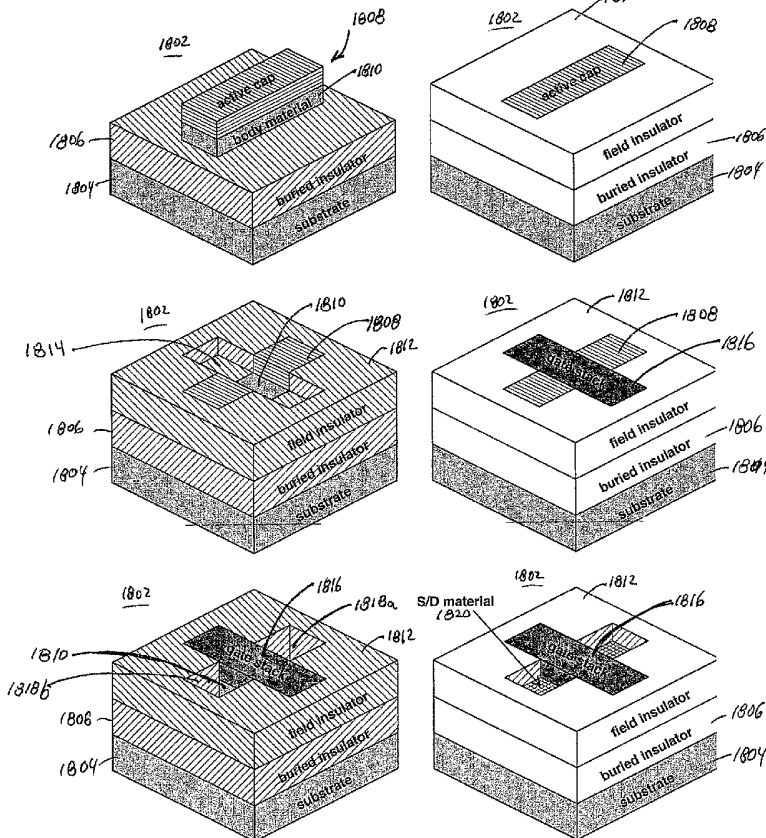
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(54) Title: PROCESS FOR FABRICATING A SELF-ALIGNED DEPOSITED SOURCE/DRAIN INSULATED GATE FIELD-EFFECT TRANSISTOR



(57) Abstract: Processes for forming self-aligned, deposited source/drain, insulated gate, transistors and, in particular, FETs. By depositing a source/drain in a recess such that it remains only in the recess, the source/drain can be formed self-aligned to a gate and/or a channel of such a device. For example, in one such process a gate structure of a transistor may be formed and, in a material surrounding the gate structure, a recess created so as to be aligned to an edge of the gate structure. Subsequently, a source/drain conducting material may be deposited in the recess. Such a source/drain conducting material may be deposited, in some cases, as layers, with one or more such layers being planarized following its deposition. In this way, the conducting material is kept within the boundaries of the recess.

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INTERNATIONAL SEARCH REPORT

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B. FIELDS SEARCHED

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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X A	US 2004/142524 A1 (GRUPP DANIEL E ET AL) 22 July 2004 (2004-07-22) figures 4,5	1-6, 10-46 7-9
X	US 5 943 575 A (CHUNG ET AL) 24 August 1999 (1999-08-24) figure 3	1-3
X	US 6 091 076 A (DELEONIBUS ET AL) 18 July 2000 (2000-07-18) paragraph '0061!; figures 9,14	1-3

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INTERNATIONAL SEARCH REPORT

Information on patent family members

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